

APPENDIX A - SPECIFICATION/CLAIM AMENDMENTS INCLUDING NOTATIONS TO INDICATE CHANGES MADE

Serial No.: 09/651,702 Docket No.: 150.00800102

Amendments to the following are indicated by underlining what has been added and bracketing what has been deleted. Additionally, all amendments have been indicated by bold font.

In the Specification

The paragraph beginning at page 14, line 21, has been amended as follows:

As illustrated in Figure 2, the components can be pre-mixed in mixing manifold 122. The components can also be heated in the mixing manifold 122 by including heating coils or vanes in walls of manifold 122 to increase heat transfer to the components before passing through an optional circulation heater 124, such as a circulation heater supplied by Watlow Co. of Saint Louis, Missouri. The organic residue removal composition then enters the pressure vessel 114 through a dispensing device 126, such as a shower-head, with at least one of the components in the supercritical state. The circulation heater 124 is preferably used to increase

In the Claims

the heating efficiency of the system when creating the supercritical composition in the mixing

manifold 122 prior to entering the pressure vessel 114[14]. The organic material removal

For convenience, all pending claims are shown below.

composition passes over the substrate 116 from the dispensing device 126.

- 19. (Amended) An organic material removal composition comprising [at least one component]sulfur trioxide (SO_3) in a supercritical state[, wherein the composition includes an oxidizer selected from the group of sulfur trioxide (SO_3), sulfur dioxide (SO_2), nitrous oxide (N_2O_3), NO, NO₂, ozone (O_3), hydrogen peroxide (H_2O_2), F_2 , Cl_2 , Br_2 , and oxygen (O_2)].
- 20. (Amended) The composition of claim 19, wherein the <u>composition further comprises</u> at least one [component in a supercritical state is the] oxidizer selected from the group

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<u>consisting</u> of [sulfur trioxide (SO₃),] sulfur dioxide (SO₂), nitrous oxide (N₂O), NO, NO₂, ozone (O₃), hydrogen peroxide (H₂O₂), F₂, Cl₂, Br₂, and oxygen (O₂).

- 21. (Amended) The composition of claim 20, wherein the at least one [component]oxidizer is in a supercritical state [is sulfur trioxide].
- 22. (Amended) The composition of claim [21]19, wherein the composition consists essentially of sulfur trioxide in the supercritical state.
- 23. (Amended) The composition of claim 19, wherein the composition [includes a supercritical] further comprises an additional component [in the supercritical state] selected from the group consisting of carbon dioxide (CO_2), ammonia (NH_3), H_2O , nitrous oxide (N_2O), carbon monoxide (N_2O), helium (N_2O), neon (N_2O), argon (N_2O), argon (N_2O), argon (N_2O), argon (N_2O).
- 24. (Amended) The composition of claim 23, wherein the <u>additional[supercritical]</u> component is carbon dioxide [and the oxidizer is sulfur trioxide].
- 25. (Amended) An organic material removal composition comprising <u>sulfur trioxide</u> (SO_3) <u>in a supercritical state and an oxidizer [in a supercritical state, wherein the oxidizer is selected from the group of sulfur trioxide</u> (SO_3), sulfur dioxide (SO_2), nitrous oxide (N_2O_3), NO, NO₂, ozone (O_3), hydrogen peroxide (O_3), O_3 , O_4 , and oxygen (O_3).
- 27. (Amended) An organic material removal composition comprising:
 a first component selected from the group <u>consisting</u> of carbon dioxide (CO₂), ammonia
 (NH₃), H₂O, nitrous oxide (N₂O), carbon monoxide (CO), nitrogen (N₂), helium (He), neon (Ne),

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argon (Ar), krypton (Kr), and xenon (Xe)[, wherein the first component is in a supercritical state]; [and]

a second component selected from the group <u>consisting</u> of [sulfur trioxide (SO_3),] sulfur dioxide (SO_2), nitrous oxide (N_2O), NO, NO₂, ozone (O_3), hydrogen peroxide (H_2O_2), F_2 , Cl_2 , Br₂, and oxygen (O_2); and

sulfur trioxide (SO₃) in a supercritical state.

- 28. The composition of claim 27, wherein the first component is carbon dioxide.
- 29. (Amended) The composition of claim 27, wherein a ratio of the [first component]sulfur trioxide to the second component [in the supercritical state] is [in the range of] about 1:100 by volume to about 100:1 by volume.
- 31. (Amended) The composition of claim [30]28, wherein a ratio of carbon dioxide:sulfur trioxide is [preferably in the range of] about 10:1 by volume to about 1:1 by volume.
- 32. (Amended) The composition of claim [30]27, wherein the [sulfur trioxide]first component is in a supercritical state.
- 33. (New) The composition of claim 27, wherein the second component is in a supercritical state.
- 34. (New) The composition of claim 27, wherein the first component and the second component are both in supercritical states.
- 35. (New) The composition of claim 23, wherein the additional component is in a supercritical state.

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36. (New) The composition of claim 19 further comprising a component selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen fluoride, ammonium fluoride, tetramethylammonium fluoride, tetramethylammonium hydroxide, beta-diketones, fluorinated-diketones, organic acids, and combinations thereof.

- 37. (New) The composition of claim 25 further comprising a component selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen fluoride, ammonium fluoride, tetramethylammonium fluoride, tetramethylammonium hydroxide, beta-diketones, fluorinated-diketones, organic acids, and combinations thereof.
- 38. (New) The composition of claim 27 further comprising a component selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen fluoride, ammonium fluoride, tetramethylammonium fluoride, tetramethylammonium hydroxide, beta-diketones, fluorinated-diketones, organic acids, and combinations thereof.